

VACUUM ARC ION SOURCES

(or “MEVVA” ION SOURCES)

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OUTLINE

- **Background**
- **The Basics**
- **Embodiments**
- **Characteristics / Parameters**
- **Applications**
- **Summary**

SUITABILITY OF THE VACUUM ARC PLASMA FOR

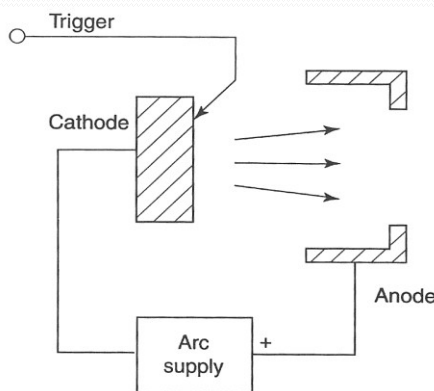
A

HIGH CURRENT METAL ION SOURCE

The plasma formed by a vacuum arc discharge is

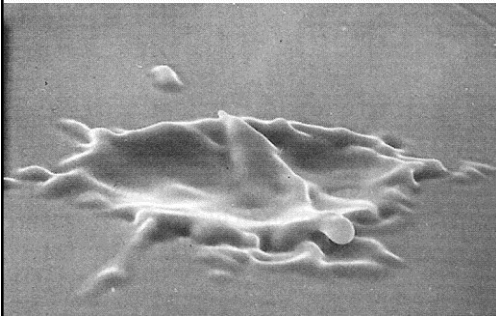
- Pure (no, or low, gas content)
- Dense
- OK for a wide range of metal species
- Simple – no tricky parts
- Simple electrical system
- Efficient – $I_{\text{ion}} / I_{\text{arc}}$ is high

THE BASIC VACUUM ARC

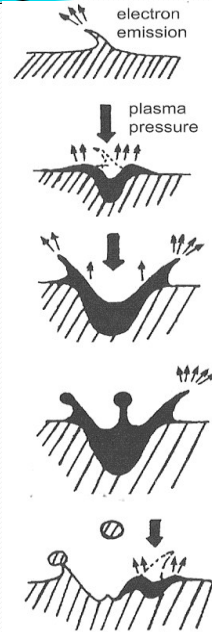


- Extreme simplicity
- Also called “cathodic arc”
- Plasma is born at the cathode and streams toward the anode
- On the cathode, the plasma emission sites are tiny “cathode spots”
- Metal plasma jets away from the spots in a manner very similar to a laser-produced plasma

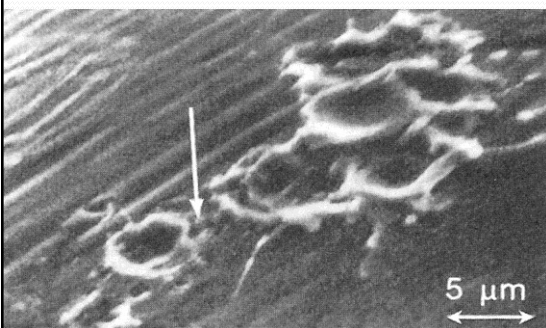
CATHODE SPOTS



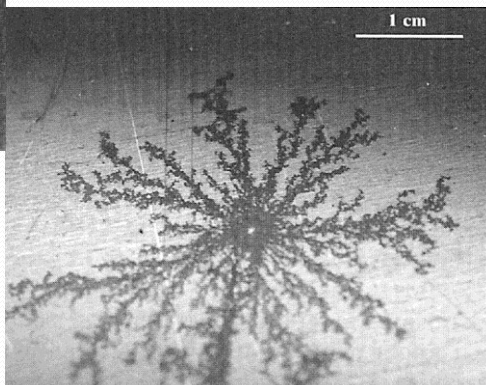
- Cathode spots are the plasma emission sites
- Each spot ejects a plasma plume quite similar to a laser-produced plasma
- Size $\sim \mu\text{ms}$, lifetime $\sim \text{secs}$ (or less)
- Current density $\sim 10^{11} \text{ A/m}^2$; Power density $\sim 10^{12} \text{ W/m}^2$
- Along with metal plasma, “macroparticles” are also formed



CATHODE SPOT MOTION



- New spots form, leaving “chicken tracks”, as seen in many plasma devices



HISTORY

- **1940s – U.S. Manhattan Project**
 - For isotope separation. Some basic studies, but work was abandoned
- **1950s & '60s – USSR (Plutto et al).**
 - Demonstration of ion extraction from the vacuum arc plasma
- **1970s – Sandia, LANL, U.K., USSR**
 - For various applications, but work was not pursued.
- **1980s – Berkeley (LBNL) and Tomsk (HCEI)**
 - More-or-less parallel & simultaneous development at both places.
 - Large sources developed and demonstrated for accelerator injection and ion implantation.
 - Ongoing programs established, including many collaborative projects.

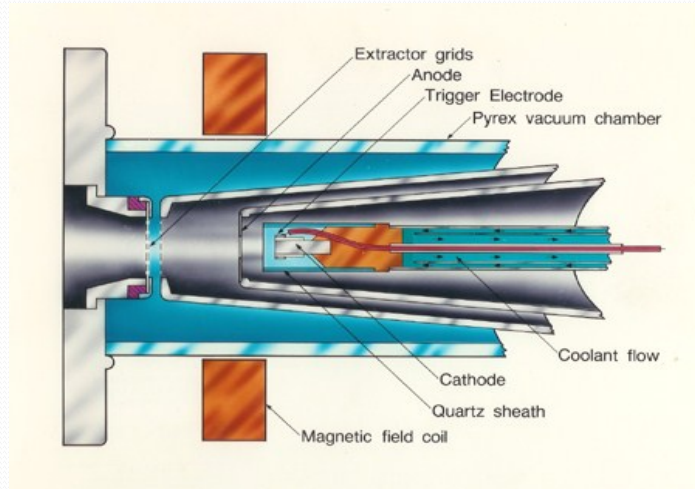
THE VACUUM ARC ION SOURCE IN ESSENCE

- **Metal plasma is formed by a vacuum arc plasma discharge**
 - Very efficient: $I_{\text{ion}} \sim (0.05 - 0.1) I_{\text{arc}}$
- **Energetic ion beam is “extracted” by beam formation electrodes**
- **The ion beam is typically**
 - Metal ions (almost all in the Periodic Table)
 - Extraction energy typically 20 – 150 keV
 - Beam current typically 10 mA – 1 A

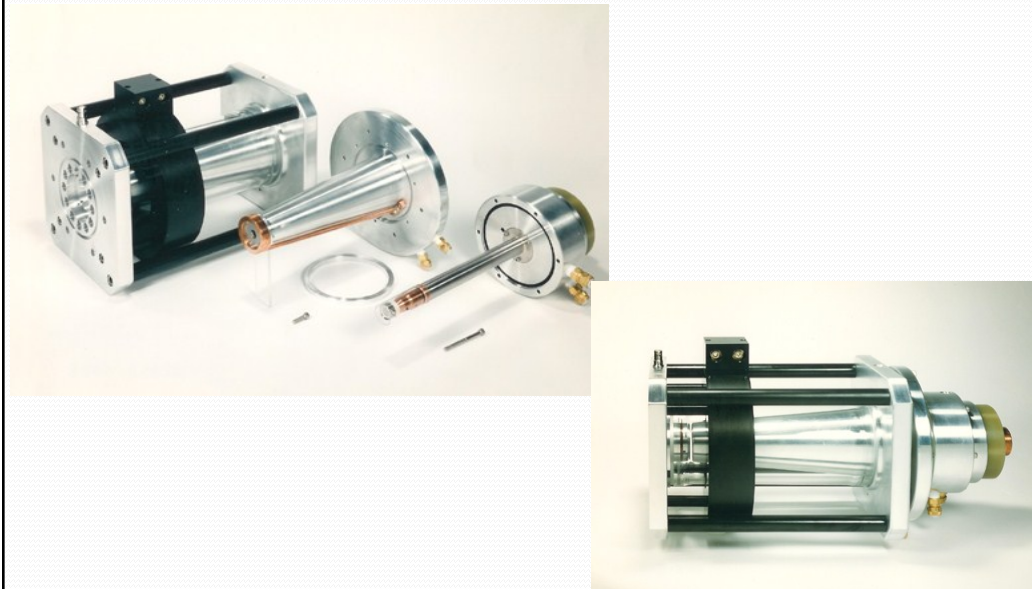
 An ion beam generator for *high current* beams of *metal* ions 

THE MEVVA II VACUUM ARC ION SOURCE

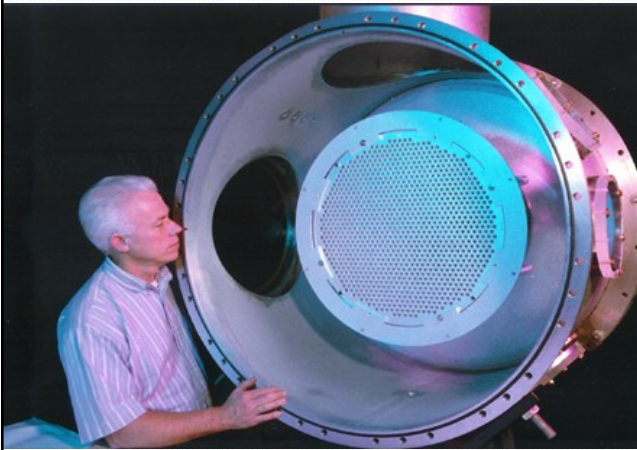
☞ Make a vacuum arc plasma and extract ions from it ☞



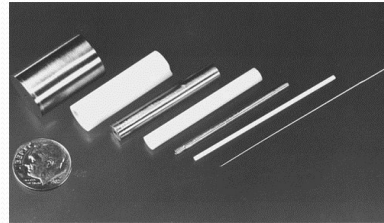
MEVVA II ION SOURCE



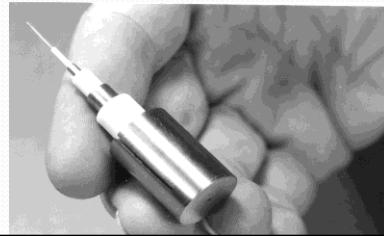
BIG & SMALL MEVVA EMBODIMENTS



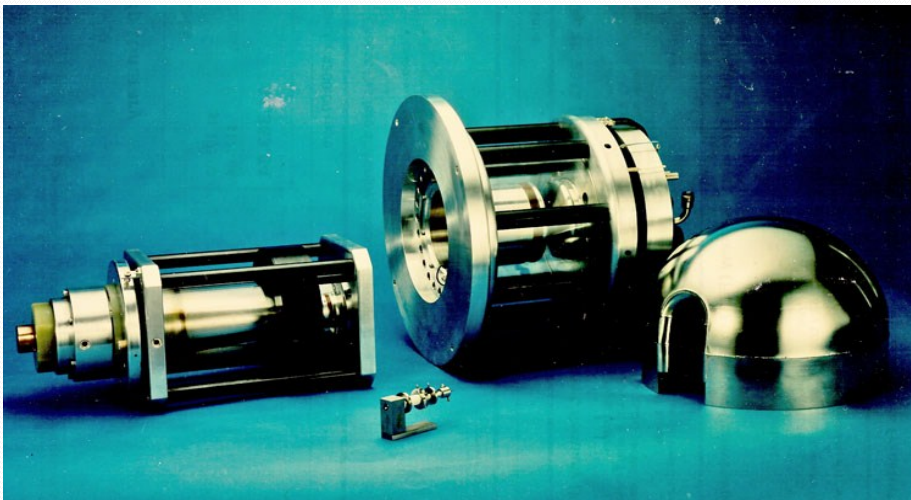
50 cm diameter extractor: 100 keV Ti ion beam with current up to ~20 A



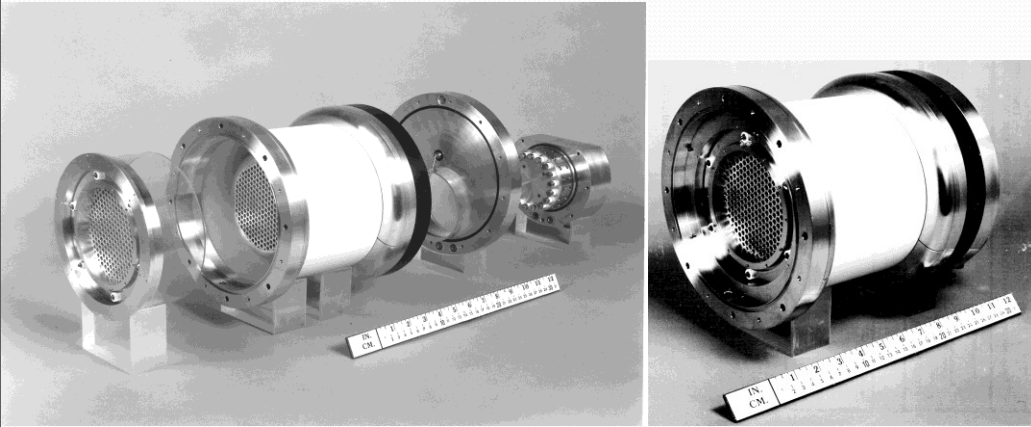
**About "thumb sized":
Short pulse, low rep rate**



MEVVA II, MEVVA IV, MINIMEVVA

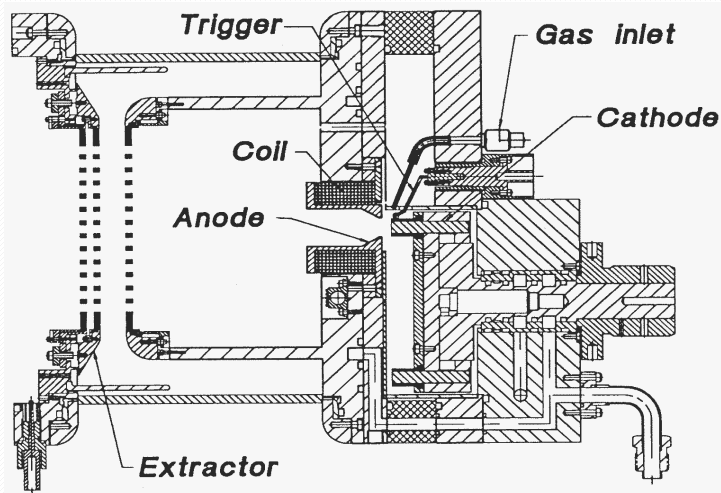


MEVVA V -- "WORKHORSE SOURCE"



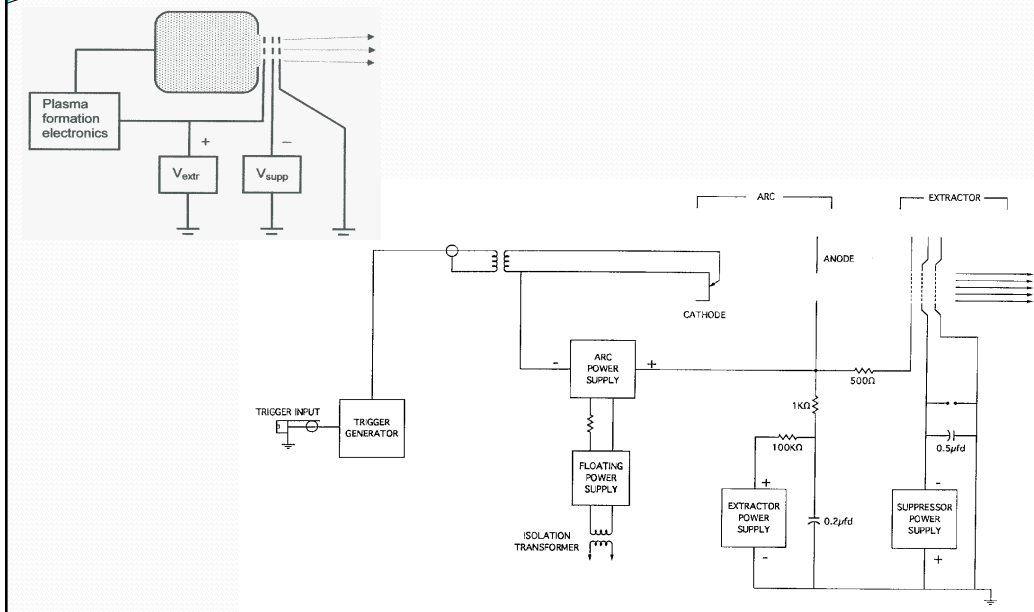
Used for ion implantation research for many years.
18 cathodes, 10 cm extractor, up to ~150 keV, ~1 A

MEVVA V SCHEMATIC



Outline of the Mevva V ion source

BASIC ELECTRICAL SCHEMATIC



ION CHARGE STATES

Ions formed in the vacuum arc plasma are in general multiply-stripped, with a mean charge state $\langle Q \rangle$ between 1 and 3.

Iridium CSD

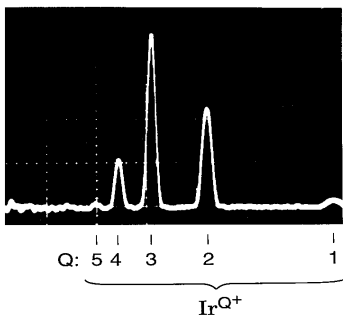


TABLE 1. Vacuum arc ion charge state distributions. [Ion charge state fractions and mean charge states, expressed in terms of particle current. * trace (under 1%).]

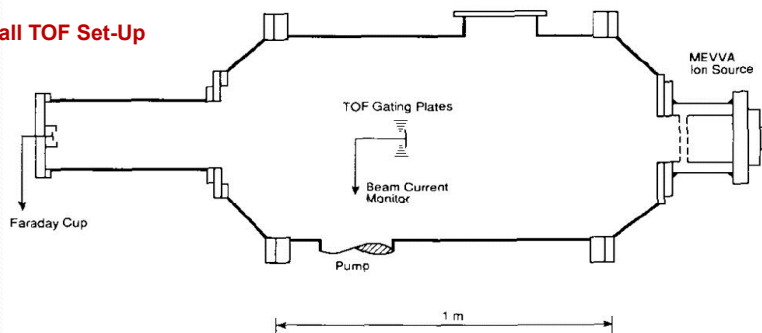
Element	Z	Q=1+	2+	3+	4+	5+	6+	\bar{Q}_p
Li	3	100						1.0
C	6	100						1.0
Mg	12	46	54					1.5
Al	13	38	51	11				1.7
Si	14	63	35	2				1.4
Ca	20	8	91	1				1.9
Sc	21	27	67	6				1.8
Ti	22	11	75	14				2.1
V	23	8	71	20	1			2.1
Cr	24	10	68	21	1			2.1
Mn	25	49	50	1				1.5
Fe	26	25	68	7				1.8
Co	27	34	59	7				1.7
Ni	28	30	64	6				1.8
Cu	29	16	63	20	1			2.0
Zn	30	80	20					1.2
Ge	32	60	40	*				1.4
Sr	38	2	98					2.0
Y	39	5	62	33				2.3
Zr	40	1	47	45	7			2.6
Nb	41	1	24	51	22	2		3.0
Mo	42	2	21	49	25	3		3.1
Pd	46	23	67	9	1			1.9
Ag	47	13	61	25	1			2.1
Cd	48	68	32					1.3
In	49	66	34	*				1.4
Sn	50	47	53					1.5
Sb	51	100	*					1.0
Ba	56		100					2.0
La	57	1	76	23				2.2
Ce	58	3	83	14				2.1
Pr	59	3	69	28				2.2
Nd	60		83	17				2.2
Sm	62	2	83	15				2.1
Gd	64	2	76	22				2.2
Dy	66	2	66	32				2.3
Ho	67	2	66	32	*			2.3
Er	68	1	63	35	1			2.4
Tm	69	13	78	9				2.0
Yb	70	3	88	8				2.1
Hf	72	3	24	51	21	1		2.9
Ta	73	2	33	38	24	3		2.1
W	74	2	23	43	26	5	1	3.1
Ir	77	5	37	46	11	1		2.7
Pt	78	12	69	18	1			2.1
Au	79	14	75	11				2.0
Pb	82	36	64					1.6
Bi	83	83	17					1.2
Th	90		24	64	12			2.9
U	92		12	58	30			3.2

TIME-OF-FLIGHT Q/A ANALYSIS SYSTEM

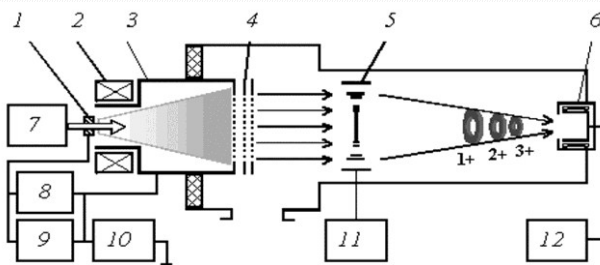
A relatively simple way of obtaining a Q/A spectrum of an ion beam:

- Gate a (sub-)microsecond piece of the beam,
- Monitor the beam components, separated according to their flight times,
- Analyze according to $\frac{1}{2}m_u Av^2 = eQV_{\text{ext}}$
- Or $t = L[2eV_{\text{ext}}(Q/Am_u)]^{-1/2}$

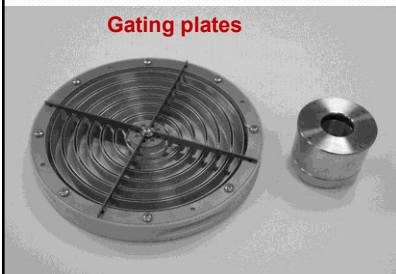
Overall TOF Set-Up



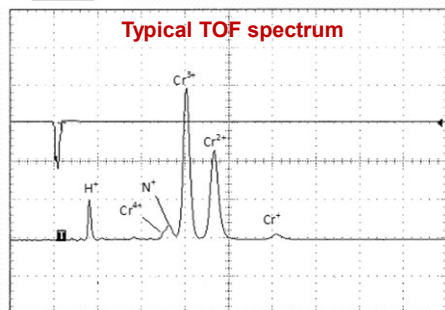
TOF SYSTEM



Gating plates



Typical TOF spectrum



TOF CSDs

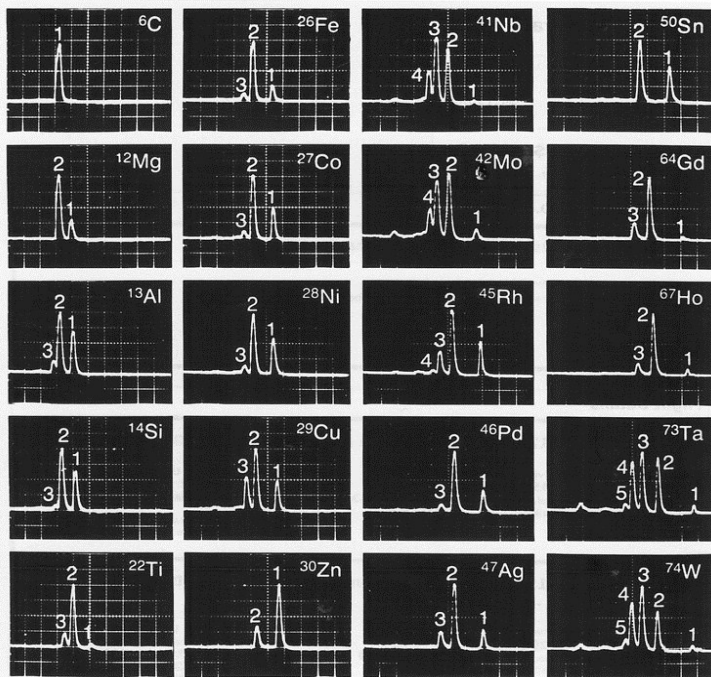
Low multiply-stripped,
typically $Q = 1, 2, 3, 4$

$\langle Q \rangle = 1$ to 3

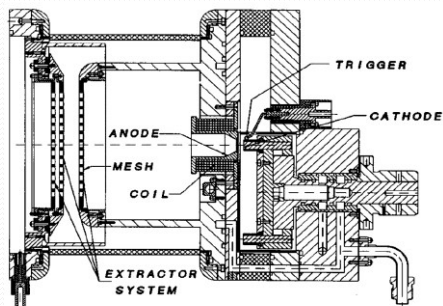
The more refractory metals
have higher Q :

$$\langle Q_p \rangle = 0.38(T_{BP}/1000) + 1$$

Low contamination

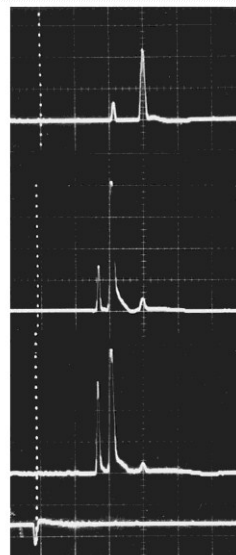


Q-CONTROL VIA B



Vacuum arc ion source with magnetic field coil.

The ion charge state can be increased by
immersing the arc in a magnetic field of up to
several kG.



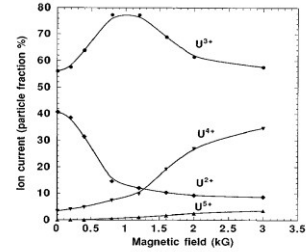
TOF charge state spectra for Bi ions (i) without magnetic field (upper) and (ii) with magnetic field (middle, $B=2$ kG; lower, $B=3.75$ kG). The spectral peaks are for charge states $Q=1+$, $2+$, and $3+$, right-to-left. The oscilloscope signals are electrical current into a Faraday cup.

B-ENHANCED CHARGE STATES

Charge state distributions and mean charge states (all in particle current fractions) for a range of metal ion species with and without magnetic field applied. $I_{arc}=220$ A, $B_{max}=3.75$ kG.

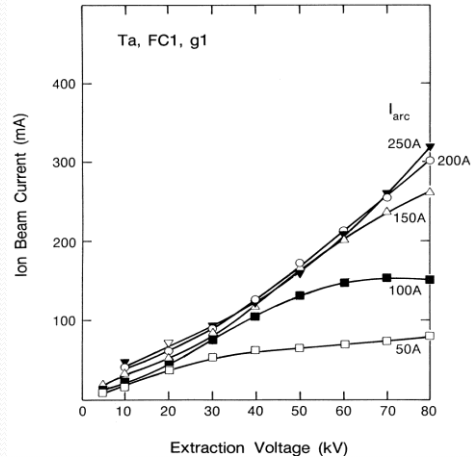
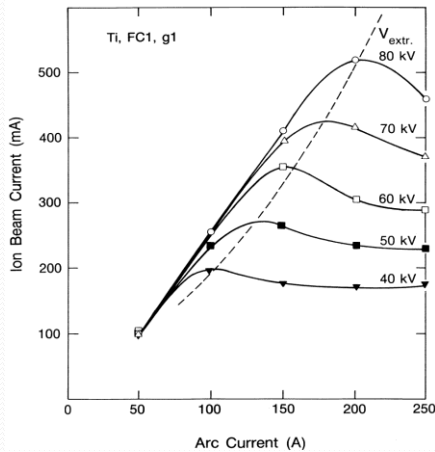
Metal	Without magnetic field					With magnetic field						\bar{Q}_2	\bar{Q}_2/\bar{Q}_1	
	1+	2+	3+	4+	5+	1+	2+	3+	4+	5+	6+			
C	96	4				1.0	60	40				1.4	1.40	
Mg	51	49				1.5	5	95				1.9	1.27	
Al	38	51	11			1.7	10	40	50			2.4	1.40	
Sc	23	66	11			1.9	16	23	59	2		2.5	1.31	
Ti	11	76	12	1		2.0	5	35	54	6		2.6	1.30	
V	11	72	15	2		2.1	13	31	48	8		2.5	1.20	
Cr	14	70	15	1		2.0	11	26	55	8		2.6	1.30	
Mn	48	52				1.5	26	47	25	2		2.0	1.33	
Fe	28	68	6			1.8	7	58	35			2.3	1.28	
Ni	43	50	7			1.6	19	62	18	1		2.0	1.25	
Co	34	59	7			1.8	9	56	31	4		2.3	1.27	
Cu	28	53	18	1		1.9	8	41	47	3	1	2.5	1.32	
Y	7	63	29	1		2.2	6	9	77	8		2.9	1.32	
Nb	3	40	39	16	2	2.7	1	9	23	52	13	2	3.7	1.37
Mo	7	30	40	20	3	2.8	5	11	26	48	10		3.5	1.25
Ba	3	97				2.0	2	41	53	3	1	2.6	1.30	
La	4	65	31			2.3	3	16	61	20		3.0	1.30	
Gd	8	81	11			2.0	1	43	41	15		2.7	1.35	
Er	8	62	30			2.2	2	12	70	16		3.0	1.36	
Hf	7	26	48	18	1	2.8	5	16	31	32	15	1	3.4	1.21
Ta	1	17	39	39	4	3.3	1	5	13	40	41	2	4.2	1.27
W	1	17	35	35	12	3.4	1	5	16	39	32	7	4.2	1.20
Pr	12	70	18			2.1	3	25	64	8		2.8	1.30	
Pb	40	60				1.6	1	75	24			2.2	1.37	
Bi	89	11				1.1	9	60	31			2.2	2.00	

Uranium



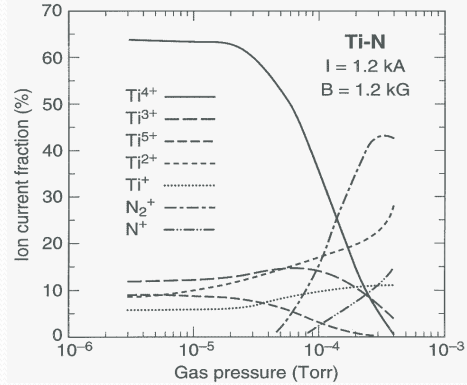
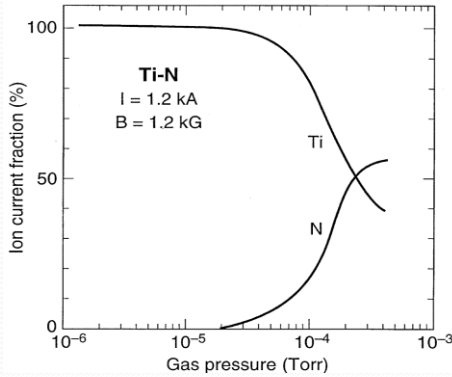
Ion beam current fractions as a function of magnetic field strength for the different ionization states of a uranium ion beam; $I_{arc}=280$ A.

BEAM CURRENT



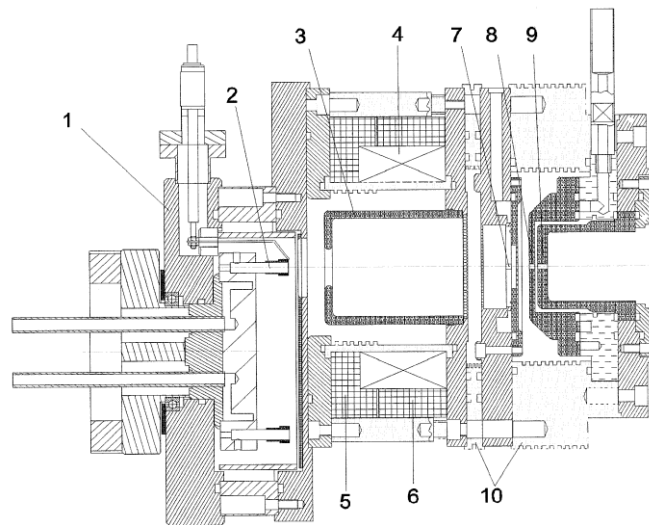
Extracted ion beam current can be a few mA up to several Amps, depending on arc current and extractor size. (Mevva IV data).

HYBRID METAL/GAS OPERATION



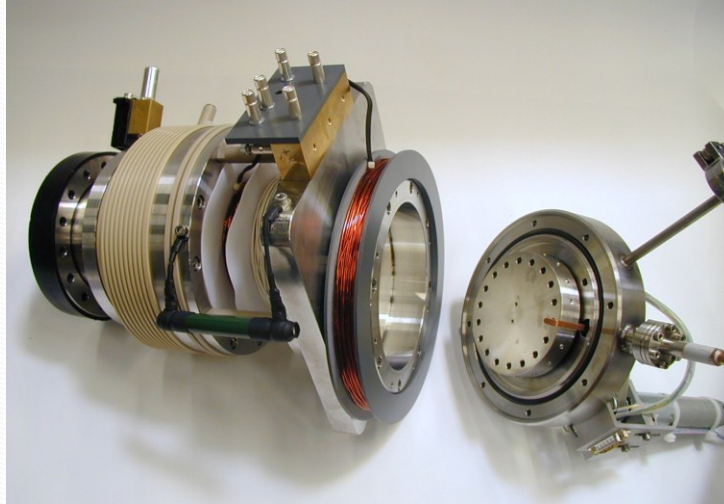
Gaseous fraction increases and charge states decrease with increasing gas pressure.

GSI SOURCE (FOR UNILAC INJECTION)



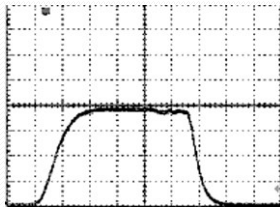
- 1 – Cathode flange
- 2 – Cathode
- 3 – Anode (stainless steel)
- 4 – 10 SmCo cusp magnets
- 5 – Coil I
- 6 – Coil II
- 7 – Plasma electrode and grid
- 8 – Screening electrode
- 9 – Ground electrode
- 10 – Insulators

GSJ VACUUM ARC SOURCE

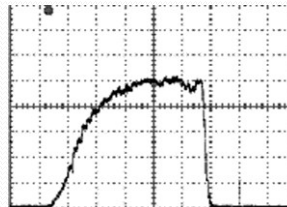


U⁴⁺ INJECTION AT GSI

- U⁴⁺ at 2.2 keV/amu matches the required RFQ injection velocity
- Beam is extracted at ~30 kV, followed by ~100 kV post-acceleration
- Beam parameters:
 - 25 mA U⁴⁺ at ~525 keV, measured at RFQ entrance
 - 56% of the extracted Mevva U beam is in U⁴⁺ charge state
 - U⁴⁺ beam noise is up to but not greater than ~10%
 - Pulse-to-pulse repeatability is good



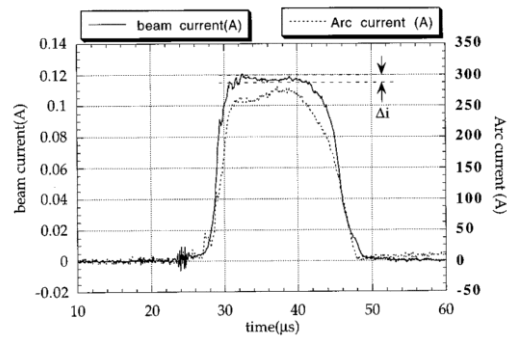
I_{ion} , total beam (all charge states)
40 mA/cm, 100 μ s/cm
30 cm from ion source



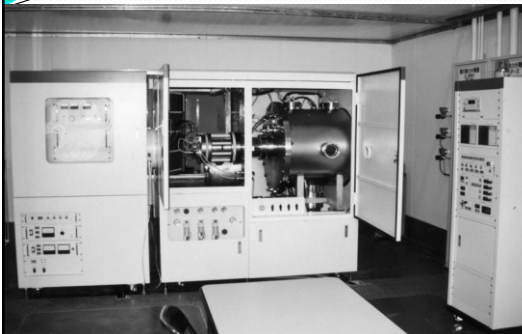
I_{ion} , U⁴⁺ only (post-analysis)
5 mA/cm, 100 μ s/cm
12 m from ion source

AS AN HIF ION SOURCE

As an example / demonstration of potential HIF application:
Gd beam (85% in the Gd^{2+} charge state),
at an ion energy of 120 keV (60 kV extraction voltage),
with a collected beam current of 120 e mA,
for a 20 μs pulse width,
a pulse rise time of < 1 μs ,
and a beam emittance about 0.3π mm. mrad (normalized).



AS A METAL ION IMPLANTER



Nagasaki implanter:
up to 80 kV
0.5 A pulsed beam current,
1 ms @ up to 20 pps,
for 10 mA average beam current
beam size >15 cm diameter

(Industrial Technology Center of Nagasaki)

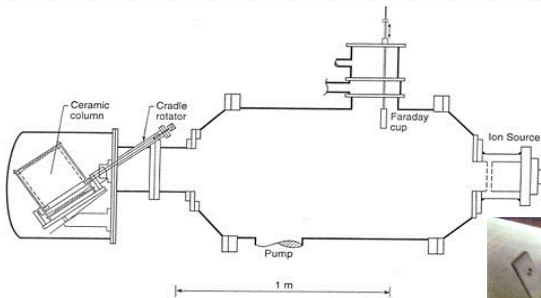


Beijing implanter:
up to 50 kV
3.3 ms @ up to 33 pps,
for 10 mA average
beam size >80cm diameter
2 m diameter vessel

(Beijing Normal University)



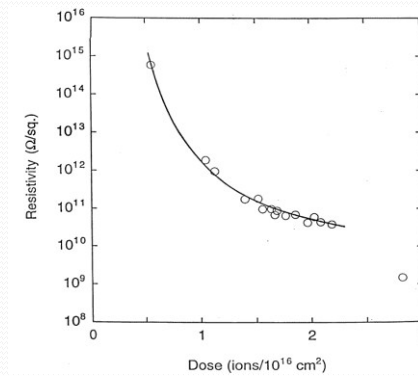
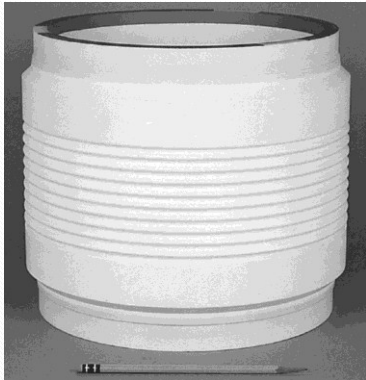
CEBAF ACCELERATOR COLUMN IMPLANT



Pt Implantation into column to grade (and thus increase) voltage hold-off



CERAMIC COLUMN RESISTIVITY TAILORING



CONCLUSION

- The vacuum arc ion source (Mevva) is unique in its
 - High current
 - of metal ions
- It is essentially a repetitively-pulsed source
- Beam noise and pulse shape irreproducibility have been greatly improved, and the source is suitable for accelerator injection
- Main demonstration of accelerator injection application is provided by GSI Darmstadt
- Other applications include metal ion implantation

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- ICIS Proceedings (Proc. Intern. Conf. Ion Sources), Special Issue of Rev. Sci. Instrum., in even-numbered-years, usually about Feb – Mar. (see also these proceedings for the latest on all ion sources).
- And all the references there-in